L Number	Hits	Search Text	DB	Time stamp
365	0	(substrate near10 temperature) and sputter\$4	USPAT;	2004/07/15 09:25
		and (pixel or cinduct\$4) and hydrogen and	US-PGPUB;	
		(vacuum adj chamber)and 204-205/\$.ccls.	EPO; JPO; DERWENT;	
:			IBM_TDB	
367	0	(substrate near10 temperature) and sputter\$4	USPAT;	2004/07/15 10:02
	-	and (pixel or cinduct\$4) and hydrogen and	US-PGPUB;	
		(vacuum adj chamber)and 205/\$.ccls.	EPO; JPO;	
			DERWENT;	
			IBM_TDB	0004/07/75 00 00
366	13	(substrate near10 temperature) and sputter\$4	USPAT;	2004/07/15 09:26
		and (pixel or cinduct\$4) and hydrogen and (vacuum adj chamber)and 204/\$.ccls.	US-PGPUB; EPO; JPO;	
		(Vacuum ad) Chambel/and 204/5.ccis.	DERWENT;	
			IBM TDB	
371	366	204/192.29	USPAT;	2004/07/15 10:02
			US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	0004/05/15 10 00
372	605	204/192.35	USPAT;	2004/07/15 10:02
			US-PGPUB; EPO; JPO;	İ
			DERWENT;	
			IBM TDB	
373	346	205/223	USPAT;	2004/07/15 10:02
3,3	3.0	200, 220	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
376	0	(substrate near10 temperature) and sputter\$4	USPAT;	2004/07/15 10:03
		and (pixel or cinduct\$4) and hydrogen and	US-PGPUB;	:
		(vacuum adj chamber)and 205/223	EPO; JPO; DERWENT;	
			IBM TDB	
375	1	(substrate near10 temperature) and sputter\$4	USPAT;	2004/07/15 10:03
9.0		and (pixel or cinduct\$4) and hydrogen and	US-PGPUB;	
İ	•	(vacuum adj chamber)and 204/192.35	EPO; JPO;	
1			DERWENT;	
	_	( )	IBM_TDB	2004/07/15 10:03
374	4	(substrate near10 temperature) and sputter\$4	USPAT; US-PGPUB;	2004/07/15 10:03
		and (pixel or cinduct\$4) and hydrogen and (vacuum adj chamber)and 204/192.29	EPO; JPO;	
		(vacuum auj chamber)and 204/192.29	DERWENT;	
			IBM TDB	
- 1	1151	349/143	USPAT;	2003/03/07 14:47
			US-PGPUB;	
			JPO	0000/00/05 10 17
-	664	349/187	USPAT;	2003/03/06 13:17
			US-PGPUB;	
<u>_</u>	1050	349/43	USPAT;	2004/07/14 09:26
	1030	337/13	US-PGPUB;	-301, 51, 21 02.20
			JPO	
_	2141	pixel with temperature	USPAT;	2003/03/06 13:20
		-	US-PGPUB;	
			JPO	0000/00/00 == ==
-	86		USPAT;	2003/03/06 13:23
		amorphous) and (inject\$4 near\$5 hydroben	US-PGPUB;	
_	٥	near\$5 gas)   (pixel with temperature) and (pixel with	JPO USPAT;	2003/03/06 13:24
-	ľ	amorphous) and (inject\$4 near\$5 hydroben	US-PGPUB;	2005,05,00 15.24
		near\$5 gas) and (etch\$4 with (weak adj	JPO	
		acide))		
	0	(pixel with temperature) and (pixel with	USPAT;	2003/03/06 13:24
		amorphous) and (inject\$4 near\$5 hydroben	US-PGPUB;	
		near\$5 gas) and etch\$4 and 349/143	JPO	
<del>-</del>	28	(pixel with temperature) and 349/143	USPAT;	2003/03/06 13:26
			US-PGPUB;	
			JPO	L

180					
180	_	61	(pixel with amorphous) and 349/143	US-PGPUB;	2003/03/06 13:26
107   (pixel with temperature) and (pixel with   USPAT; USPAT; USPAT)   2003/03/06 14:24   2003/03/06 14:24   2003/03/06 14:24   2003/03/06 13:33   2003/03/06 13:33   2003/03/06 13:33   2003/03/06 13:34   2003/03/06 13:34   2003/03/06 13:34   2003/03/06 13:35   2003/03/06 13:3	-	180	(pixel with amorphous) and 349/43	USPAT; US-PGPUB;	2003/03/06 13:26
USPAT: USPAT:	-	107		USPAT; US-PGPUB;	2003/03/06 14:24
1	-	5558	(pixel and temperature and amorphous)	USPAT; US-PGPUB;	2003/03/06 13:33
Total	-	3907		USPAT; US-PGPUB;	2003/03/06 13:34
2855   (pixel and temperature and amorphous) and (liquid adj crystal) and substrate (pixel and temperature and amorphous) and (liquid adj crystal) and substrate and (etch\$4 with (weak adj acid))   USPAT;	-	768	(inject\$4 near\$5 (hydrogen with gas)) and	USPAT; US-PGPUB;	2003/03/06 13:35
1	-	2855	(pixel and temperature and amorphous) and (inject\$4 near\$5 (hydrogen with gas)) and	USPAT; US-PGPUB;	2003/03/06 13:36
111	_	7	(pixel and temperature and amorphous)and (inject\$4 near\$5 (hydrogen with gas)) and (liquid adj crystal) and substrate and	USPAT; US-PGPUB;	2003/03/06 16:39
TIMN TOB	-	111	(pixel with temperature) and (pixel with	US-PGPUB; EPO; JPO;	2003/10/17 17:09
- 1 5135581.pn. USPĀT; US-PGPUB; JPO USPAT;	-	7	(inject\$4 near\$5 (hydrogen with gas)) and (liquid adj crystal) and substrate and	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/03/06 16:41
- 97 (pixel with amorphous) and 349/43 and temperature temperature (pixel with amorphous) and 349/187 (pixel with temperature) and 349/187 (pixel with temperature) and 349/43 (pixel with temperature) and 349/187 (pixel with temperature) and 349/187 (pixel with temperature) and (pixel with amorphous) and (inject\$4 near\$5 hydroben near\$5 gas) and etch\$4 (pixel with temperature) and (pixel with amorphous) and (inject\$4 near\$5 hydroben near\$5 gas) and etch\$4 (pixel with temperature) and (pixel with amorphous) and (inject\$4 near\$5 hydroben near\$5 gas) and etch\$4 (pixel with temperature) and (pixel with amorphous) and (inject\$4 near\$5 hydroben near\$5 gas) and etch\$4 and (vacuum adj chamber) (pixel with amorphous) and (vacuum adj chamber) (pixel with amorphous) and (vacuum adj chamber) (pixel with amorphous) and (vacuum adj chamber) (pixel with amorphous) and (vacuum adj chamber) (pixel with amorphous) and (vacuum adj chamber) (pixel with amorphous) and (vacuum adj chamber) (pixel with amorphous) and (vacuum adj chamber) (pixel with amorphous) and (vacuum adj chamber) (pixel with amorphous) and (vacuum adj chamber) (pixel with amorphous) and (vacuum adj chamber) (pixel with amorphous) and (vacuum adj chamber) (pixel with amorphous) (pixel with amorpho	-	1	5135581.pn.	USPAT; US-PGPUB;	2004/02/20 10:48
- 29 (pixel with amorphous) and 349/187  - 62 (pixel with temperature) and 349/43  - 7 (pixel with temperature) and 349/187  - 7 (pixel with temperature) and (pixel with amorphous) and (inject\$4 near\$5 hydroben near\$5 gas) and etch\$4  - 7 (pixel with temperature) and (pixel with amorphous) and (inject\$4 near\$5 hydroben near\$5 gas) and etch\$4  - 7 (pixel with temperature) and (pixel with amorphous) and (inject\$4 near\$5 hydroben near\$5 gas) and etch\$4  - 12 (pixel with temperature) and (pixel with amorphous) and (inject\$4 near\$5 hydroben near\$5 gas) and etch\$4 and (vacuum adj chamber)  - 12 (pixel with temperature) and (pixel with amorphous) and (vacuum adj chamber)  - 12 (pixel with temperature) and (pixel with amorphous) and (vacuum adj chamber)  - 1 20020085168.pn.  - 1 5135581.pn 1 6433842.pn 293 349/43 and passivation and (contact adj hole) near10 (drain adj electrode)  - 287 349/43 and passivation and (contact adj hole) near10 (drain adj electrode) us-pGPUB;  - 287 349/43 and passivation and (contact adj hole) near10 (drain adj electrode) us-pGPUB;  - 287 349/43 and passivation and (contact adj hole) near10 (drain adj electrode) us-pGPUB;	-	97		USPAT; US-PGPUB;	2003/03/07 15:29
- 62 (pixel with temperature) and 349/43  - 27 (pixel with temperature) and 349/187  - 27 (pixel with temperature) and (pixel with amorphous) and (inject\$4 near\$5 hydroben near\$5 gas) and etch\$4  - 7 (pixel with temperature) and (pixel with amorphous) and (inject\$4 near\$5 hydroben near\$5 gas) and etch\$4  - 7 (pixel with temperature) and (pixel with amorphous) and (inject\$4 near\$5 hydroben near\$5 gas) and etch\$4 and (vacuum adj chamber)  - 12 (pixel with temperature) and (pixel with amorphous) and (vacuum adj chamber)  - 12 (pixel with temperature) and (pixel with amorphous) and (vacuum adj chamber)  - 13 (20020085168.pn.  - 14 (5135581.pn 15 (6433842.pn 16 (6433842.pn 293 (349/43 and passivation and (contact adj hole) near10 (drain adj electrode)  - 287 (349/43 and passivation and (contact adj hole) near10 (drain adj electrode) and pixel  - 2003/10/17 16:50  - 2003/10/17 16:51  - 2003/10/17 16:57  - 2003/10/17 16:59  - 2003/10/17 16:59  - 2003/10/17 16:59  - 2003/10/17 16:59  - 2003/10/17 16:59  - 2003/10/17 16:59  - 2003/10/17 16:50  - 2003/10/17 16:51  - 2003/10/17 16:57  - 2003/10/17 16:59  - 2003	-	29	(pixel with amorphous) and 349/187	USPAT; US-PGPUB;	2003/03/07 16:34
S4	-	62	(pixel with temperature) and 349/43	USPAT; US-PGPUB;	2003/03/07 16:50
amorphous) and (inject\$4 near\$5 hydroben near\$5 gas) and etch\$4  (pixel with temperature) and (pixel with amorphous) and (inject\$4 near\$5 hydroben near\$5 gas) and etch\$4 and (vacuum adj chamber)  (pixel with temperature) and (pixel with amorphous) and etch\$4 and (vacuum adj chamber)  (pixel with temperature) and (pixel with amorphous) and (vacuum adj chamber)  2003/10/17 17:10  USPAT; USPAT; USPAT; IBM_TDB USPAT; IBM_TDB USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; USPAT 2004/02/20 09:07  1 5135581.pn. USPAT 2004/02/20 09:22  1 6433842.pn. USPAT 2004/02/20 09:35  293 349/43 and passivation and (contact adj USPAT; DO 104/07/14 09:28 hole) near10 (drain adj electrode) USPAT; DO 104/07/14 09:28 hole) near10 (drain adj electrode) and pixel US-PGPUB; DO 105-07/14 09:28	-	27	(pixel with temperature) and 349/187	USPAT; US-PGPUB;	2003/03/07 16:51
amorphous) and (inject\$4 near\$5 hydroben near\$5 gas) and etch\$4 and (vacuum adj chamber)  12 (pixel with temperature) and (pixel with amorphous) and (vacuum adj chamber)  12 (pixel with temperature) and (pixel with amorphous) and (vacuum adj chamber)  13 20020085168.pn.  14 20020085168.pn.  15 135581.pn.  16 433842.pn.  16 433842.pn.  293 349/43 and passivation and (contact adj hole) near10 (drain adj electrode)  287 349/43 and passivation and (contact adj hole) near10 (drain adj electrode) and pixel  2004/07/14 09:28 US-PGPUB; hole) near10 (drain adj electrode) and pixel	-	54	amorphous) and (inject\$4 near\$5 hydroben	US-PGPUB;	2003/10/17 16:57
- 12 (pixel with temperature) and (pixel with uspat; amorphous) and (vacuum adj chamber)  - 1 20020085168.pn.  - 1 20020085168.pn.  - 1 5135581.pn 1 6433842.pn 293 349/43 and passivation and (contact adj hole) near10 (drain adj electrode)  - 287 349/43 and passivation and (contact adj hole) near10 (drain adj electrode) and pixel  - 287 349/43 and passivation and (contact adj hole) near10 (drain adj electrode) and pixel  - 287 349/43 and passivation and (contact adj hole) near10 (drain adj electrode) and pixel  - 287 349/43 and passivation and (contact adj hole) near10 (drain adj electrode) and pixel  - 287 349/43 and passivation and (contact adj hole) near10 (drain adj electrode) and pixel	-	7	(pixel with temperature) and (pixel with amorphous) and (inject\$4 near\$5 hydroben near\$5 gas) and etch\$4 and (vacuum adj	US-PGPUB;	2003/10/17 16:59
- 1 20020085168.pn. USPĀT; US-PGPUB - 1 5135581.pn. USPĀT - 1 6433842.pn. USPĀT - 293 349/43 and passivation and (contact adj hole) near10 (drain adj electrode) USPĀT; hole) near10 (drain adj electrode) USPĀT; US	-	12	(pixel with temperature) and (pixel with	US-PGPUB; EPO; JPO; DERWENT;	2003/10/17 17:10
- 1 6433842.pn. 293 349/43 and passivation and (contact adj hole) near10 (drain adj electrode)  - 287 349/43 and passivation and (contact adj hole) near10 (drain adj electrode) 4 hole) near10 (drain adj electrode) 4 hole) near10 (drain adj electrode) 4 USPAT; 4 hole) near10 (drain adj electrode) 4 USPAT; 4 USPAT; 4 USPAT; 4 DSPAT; 4 D	-		-	USPAT; US-PGPUB	
- 293 349/43 and passivation and (contact adj USPAT; hole) near10 (drain adj electrode) US-PGPUB; JPO - 287 349/43 and passivation and (contact adj USPAT; hole) near10 (drain adj electrode) and pixel US-PGPUB;	-	1		ì	1
hole) near10 (drain adj electrode)  - 287 349/43 and passivation and (contact adj USPAT; 2004/07/14 09:28 hole) near10 (drain adj electrode) and pixel US-PGPUB;	-			1	
- 287 349/43 and passivation and (contact adj USPAT; 2004/07/14 09:28 hole) near10 (drain adj electrode) and pixel US-PGPUB;	-	293		US-PGPUB;	2004/07/14 09:28
	-	287		USPAT; US-PGPUB;	2004/07/14 09:28

			1110010	0001/00/00 00 55
-	245	349/43 and passivation and (contact adj	USPAT;	2004/07/14 09:56
		hole) near10 (drain adj electrode) and (pixel	US-PGPUB;	
	_	near10 (contact adj hole))	JPO	
-	0		USPAT;	2004/07/14 09:59
		hole) near10 (drain adj electrode) and (pixel	US-PGPUB;	
		near10 (contact adj hole) near10 (vacuum adj	JPO	
		chamber))		
-	1		USPAT;	2004/07/14 10:00
		(drain adj electrode) and (pixel near10	US-PGPUB;	
	}	(contact adj hole) near10 (vacuum adj	JPO	
		chamber))		
-	2		USPAT;	2004/07/14 10:13
		(drain adj electrode) and (pixel	US-PGPUB;	
		near10(vacuum adj chamber))	JPO	
-	726	((pixel or conduct\$4) near10 (vacuum adj	USPAT;	2004/07/14 10:23
	}	chamber))and sputter\$4	US-PGPUB;	
	1		JPO	
-	25	((pixel or conduct\$4) near10 (vacuum adj	USPAT;	2004/07/14 11:39
		chamber))and (sputter\$4 near10 hydrogen)	US-PGPUB;	
			JPO	
-	130144	substrate near10 temperature	USPAT;	2004/07/14 11:40
			US-PGPUB;	
			JPO	
-	34959	(substrate near10 temperature) and sputter\$4	USPAT;	2004/07/14 11:41
			US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	2004/07/14 11 41
-	4237		USPAT;	2004/07/14 11:41
		and (pixel or cinduct\$4)	US-PGPUB;	
			EPO; JPO; DERWENT;	
	ł		1	
	2252	/substants manual temporature) and southerd	IBM_TDB	2004/07/14 11:42
-	2358		USPAT;	2004/0//14 11:42
		and (pixel or cinduct\$4) and hydrogen	US-PGPUB; EPO; JPO;	
			DERWENT;	
			IBM TDB	
	262	(substrate pearly temperature) and southers	USPAT;	2004/07/15 09:25
_	262	(substrate near10 temperature) and sputter\$4 and (pixel or cinduct\$4) and hydrogen and	US-PGPUB;	2004/07/13 09:23
		(vacuum adj chamber)	EPO; JPO;	
		(vacuum auj chamber)	DERWENT;	
			IBM TDB	
i	1		1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1	L